

AMENDMENTS TO THE SPECIFICATION:

Please amend the first paragraph on page 1 after the title as follows:

The present application is a continuation-in-parts of U.S. Application Serial No. 09/509,080 filed March 22, 2000, entitled AN APPARATUS FOR INTEGRATED MONITORING OF WAFERS AND FOR PROCESS CONTROL IN THE SEMICONDUCTOR MANUFACTURING AND A METHOD FOR USE THEREOF, now U.S. Patent No. 6,426,502, which is the National Stage of International Application No. PCT/IL99/00598, filed November 7, 1999, which claims the benefit of Israeli Patent Application No. 126949, filed November 8, 1998.